

Amendments to the Claims:

This listing of claims will replace all prior versions, and listings, of claims in the application:

Listing of Claims:

1. (Cancelled)
2. (Currently Amended) A substrate cleaning apparatus comprising:
a processing bath to be filled with a cleaning chemical;
an ultrasonic oscillator disposed in the processing bath and immersed in the cleaning chemical; and
a retainer for retaining a substrate to be immersed in the cleaning chemical such that ultrasonic waves originating from the ultrasonic oscillator are radiated onto a back surface of the substrate[.]; and
propagation control apparatus for scattering or damping ultrasonic waves originating from the ultrasonic oscillator,
wherein the ultrasonic oscillator has a plurality of oscillation sources disposed in a uniformly dispersed manner.
3. (Previously Presented) A substrate cleaning apparatus comprising:
a processing bath to be filled with a cleaning chemical;
an ultrasonic oscillator disposed in the processing bath and immersed in the cleaning chemical;
a retainer for retaining a substrate to be immersed in the cleaning chemical such that ultrasonic waves originating from the ultrasonic oscillator are radiated onto a back surface of the substrate; and
a rotary mechanism for rotating the substrate retained by the retainer.
4. (Currently Amended). A substrate cleaning apparatus comprising:
a processing bath to be filled with a cleaning chemical;
an ultrasonic oscillator disposed in the processing bath and immersed in the cleaning chemical;

a retainer for retaining a substrate to be immersed in the cleaning chemical such that ultrasonic waves originating from the ultrasonic oscillator are radiated onto a back surface of the substrate; and

propagation control apparatus for scattering or damping ultrasonic waves originating from the ultrasonic oscillator; and

a rotary mechanism for rotating the substrate retained by the retainer.

5. (Previously Presented) A substrate cleaning apparatus comprising:

a processing bath to be filled with a cleaning chemical;

an ultrasonic oscillator disposed in the processing bath and immersed in the cleaning chemical;

a retainer for retaining a substrate to be immersed in the cleaning chemical such that ultrasonic waves originating from the ultrasonic oscillator are radiated onto a back surface of the substrate; and

a propagation control apparatus for scattering or damping ultrasonic waves originating from the ultrasonic oscillator, wherein the propagation control apparatus is constituted by means of placing, in a propagation path of ultrasonic waves, a plate-like member having a plurality of openings selectively formed therein.

6. (Original). The substrate cleaning apparatus according to claim 4, wherein the propagation control means includes jet nozzles for squirting a chemical in the propagation path of ultrasonic waves, thus circulating a flow of chemical.

7-13. (Cancelled)